

Let Is m be the wwwent from Semiconductor to metal and Imms be the wwwent from metal to some conductor

The second that 
$$E_{\kappa}$$
 and  $E_{\kappa}$  are gion  $e^{2\pi i k}$  and  $e^{2\pi i k}$  and

At zuwo biased,

I'I found bound (I

n = Nc. exp [- c PBn KT]

We kyw Is-m = - neAVT - 1

Aug. Thermal velocity of & is VT= - T(2KT | TIMM) - 2

deling @ un ()

more wife and

32000 701

Isom = nealakt/Tmm

=> Is->m = 1 nea TakT/ Time from sight to left and left to right]

Lid bourt.

=> I<sub>8</sub>→ m= A[4πem<sub>n</sub>k²/n³]. T². exp [-e \$ Bm/KT]

Name: Rogini Strauma in : 8120062

2) Forward based Iv Is -> m = ART2. exp (-c (PBm-VF)/KT) Isom = Ie exp [eve | KT] VF in applied to metal eide. I barriers height is reduced from 9 pm to 9 pm - VF but Im -> 8 demains constants (ie e\_ > Io) Imess = lo Italel = Ism+ Im-s = Io exp [eV=/kT]-Io 3) Removed Biased Iv. barnier height I do Clen + VR, so. Is->m = ART 2 ext (-e (OBn + VR) /RT) = Io'exp [-evr/RT] VR = - VR. So, Is-sm = Is exp (eUr/kr) But Im-s = - To ( seman could) = Io lexp (eve (kT)-1] Name: Ragini Shauns , Forward leial V 10: B120062

Schottky diode P-N diode Feature It occurs due to the It occurs due to 1 Formand Cument diffusion amunts. thermionie emission (mogainty counter teamsfort) (minority counter tu amefort). 2 Revoue Lowent It is generated only It is generated du due to majarity courto miniorally colours diffusing to the disthe barrier (It depen letion layer and de less on temperature). digting to attrue eide (defonds more on temps. (3) Speed It has high suitching It is limited by speed due to majoraly recombination time awier transfort. of injection miniation No recombination deme Carriers needed. (P) (vit - un waltage It is large about It is small about OTV. 0.3V · It is about I due to It is about 1.2 3) Ideality factor no recombination in deflation layer. to 2.0 due to secombination un defletion layer.

Name: hagini Shorm